

(19) (KR)  
(12) (A)

(51) Int. Cl.<sup>7</sup>  
B32B 15/04

(11)  
(43)

10-2004-0010234  
2004 01 31

(21) 10-2003-0048807  
(22) 2003 07 16

(30) 0202230-9 2002 07 16 (SE)

(71) , , -737 82

(72) -73741 11

-73731 20

(74)

:

(54) P V D

X- , 가 , (Ti, AL)(O, N) .

1

1 , P X- 가 , A SPIVV [1, 2], H , B .

2 SEM- .

3 - 2 X- ( 20 ° < 2 < 90 ° ).

(cemented carbide), (cermet), (cubic boron nitride; CBN)  
 가  
 (Ti, Al)(O, N)  
 4,474,849 (toughness)  
 (alumina)  
 N<sub>x</sub>) 5,330,853 1 2 3 (TiAl)  
 2 (TiAlN<sub>y</sub>) (sputtering) TiAl  
 5,549,975 (Ti, Me) N 가  
 Me 700 1  
 1 5,503,912 1 IVa, Va, VIa (ultra-thin layer)  
 (carbonitride)  
 가 0.2 - 50 nm X- TiN AlN  
 2 5,879,823 , IVB 가 - 6,254,984 4a, 5a, 6a  
 1 4a, 5a, 6a 2 가  
 2 1  
 6,071,560 , X MeX , MeX , X- Me (200)  
 Al)O<sub>2</sub> (R. Luthier and F. Levy, J. Vac. Sci. Technol., A9 (1) (1991) 102) TiN-Al<sub>2</sub>O<sub>3</sub>  
 rf TiAlON (Ti, Al)N<sub>x</sub> (Ti,  
 XRD (hump)  
 가 (K. Kawata, H. Sugimura, and O. Takai, Thin Solid Films 390 (2001) 64)  
 (PACVD) Ti-Al-O-C-N  
 (Ti, Al)N  
 (Munz et al, J. Vac. Sci. Technol. 4 (6) (1986)2717-2727 ).

가 (roughness),

가

0.3 - 20  $\mu\text{m}$ , 0.3 - 10  $\mu\text{m}$  0.5 - 20  $\mu\text{m}$

, Cu K ( = 1.54  $\text{\AA}$  ) (P)가 ( 3 ). SPVII- (B), (H), [1, 2]

(Chebychev) [1, 2](B)  $20^\circ < 2 < 60^\circ$

,  $H > 3B$  ,  $P > 5B$  ,  $0.75 < P/H < 3$

(Ti, Al)N- (NaCl) (Ti, Al)(N, O)-

$20^\circ < 2 < 48^\circ$   $4^\circ < \text{FWHM} < 7^\circ$  , 1.9

$\text{\AA}$  가 4.4  $\text{\AA}$  , 2.5  $\text{\AA}$   $30^\circ < 2 < 40^\circ$  ,  $32^\circ < 2 < 38^\circ$  (Bragg)

(Ti, Al)N NaCl- , Cu-K - 2  $2 = 37.5^\circ, 43.5^\circ, 63.5^\circ$

$^\circ$  (111)-, (200)-, (220)-

(interlayer)

가 가

(Ti, Al)(O, N)- (stylus metho

d) 2.5 mm  $R_a < 0.2 \mu\text{m}$

(Ti<sub>x</sub>Al<sub>1-x</sub>)(O<sub>y</sub>N<sub>1-y</sub>) , 10 kV ZAF 25 mm EDX

$0.20 < x < 0.70$   $0.15 < y < 0.35$ ,  $0.25 < x < 0.55$   $0.20 < y < 0.30$

, N<sub>2</sub>, O<sub>2</sub>, Ar 6 x 100 A (I<sub>EVAP</sub>) R<sub>Me</sub> = Ti

%at/(Ti%at + Al%at)- ,  $0.20 < R_{\text{Me}} < 0.70$  ,  $1.0 < P < 10 \text{ Pa}$  (P)

R<sub>Gas</sub> = O<sub>2</sub> / (N<sub>2</sub> + O<sub>2</sub>),  $0.05 < R < 0.15$  TiAl - (arc-evaporation)

가 (U<sub>BIAS</sub>)  $30 < U_{\text{BIAS}} < -600 \text{ V}$

가 ,

\_\_\_\_\_1

(Ti, Al)(O, N)- 가

6 % Co 94 % WC 가 (batch) 가

가

100 mm

20 가 가

(Ti, Al)(O, N)- 가 R<sub>Gas</sub> = O<sub>2</sub> / (N<sub>2</sub> + O<sub>2</sub>), R<sub>Gas</sub> = 0, 0.026, 0.079, 0.18, 0.2

4 . 2 6 x 100A , -120 V , 2.0 Pa .  
 520 .  
 4.0 μm .  
 1.2 mA/cm<sup>2</sup> .

XRD , 가 , EDX  
 10%at, 22%at O<sub>2</sub> / ( N<sub>2</sub> + O<sub>2</sub> ) = 0.079, 0.18 가

SEM , 2%at 10%at , O<sub>2</sub> / ( N<sub>2</sub> + O<sub>2</sub> ) = 0 0.026 가 .  
 (H/B) 가

(Young's modulus) (nanoindentation) 가 , 가

(reve test) . 10 - 100 N  
 (> 60 N) ,

(R<sub>a</sub>) AFM( (Perthometer instrument) (Atomic Force Microscope)) 가 Ra < 5 nm ,

( 1 ) .

가 가 가

1. (Ti, Al)(O, N)

	O <sub>2</sub> / ( N <sub>2</sub> + O <sub>2</sub> )	H [GPa]	E [GPa]	Ra [μm]	H/B	P/B	
1a	0	34.7	600	0.26	1.9	12.1	
1b	0.026	28.8	420	0.16	1.5	29.9	
1c	0.079	31.1	440	0.15	5.8	6.5	< 0.1 μm
1d	0.18	N/A	N/A	0.12	4.7	20.2	< 0.1 μm
1e	0.24	N/A	N/A	0.09	2.9	38.2	< 0.1 μm

2

1 (insert) , (Ti, Al)(O, N)  
 (Ti, Al)N- 2

가 1 N<sub>2</sub> - 2.0 Pa  
 TiAl 6 520 . -120 V , 6 x 10  
 OA 2.0 μm .

2 1 1c .

4.0 μm .

XRD

2a

3

6 % Co, 0.5 % TaC, 93.5 % WC  
(SS1672, AISI-1042, DIN-Ck 45).

:

1, 2, TiN (Ti, Al)

SNUN120408

250 m/min

1.5 mm

0.35 mm

( )

1a 20

1b 28

1c 32

1d 16

1e 10

2a 22

TiN 12

(Ti, Al)N 18

4

13 % Co, 87 % WC 1 2  
(SS2343, AISI-316, DIN-X5 CrNiMo 17 13  
3).

XOMX090308TR-ME06

260 m/min

3.0 mm

0.23 mm

5 mm

(build up) 가 (chipping) 가  
 2 가  
 ( )

1a 14

1b 12

1c 12

1d 8

1e 6

2a 16

TiN 8

(Ti, Al)N 14

\_\_\_\_\_ 5

10 % Co, 90 % WC

1 2  
 (SS1672, AISI-1042, DIN-Ck 45).

SD 25-6, 0-32-6R5

80 m/min

24 mm

0.16 mm

( )

1a 1000

1b 1200

1c 1600

1d 600

1e 200

2a 1000

[1] Bruker AXS (2000)

Topas V2.0 :

- , Bruker AXS, Karlsruhe,

[2] Cheary, R.W., Coelho, A.A. (1992)

X- (fitting)

- J. Appl. Cryst., 25, 109-121

, 가 .

(57)

1. X- , (P) (H),  $H > 3B$ ,  $P > 5B$ ,  $0.75 < P/H < 3$
2. 1 , ,
3. 1 2 , (Ti, Al)(O, N)
4. 3 , (Ti, Al)(O, N)-  $(Ti_x Al_{1-x})(O_y, N_{1-y})$   $0.20 < x < 0.70$   $0.15 < y < 0.35$ 가
5. 1 4 ,
6. 1 5 , ,
7. 가 (Ti, Al)(O, N) ,  $1.0 < P < 10$  Pa (Ti, Al)(O, N)  $R = 0.2 / (N_2$   
 $+ O_2)$ ,  $0.05 < R < 0.15$   $N_2, O_2, Ar$  TiAl- -

